

<b>Notice of References Cited</b>	Application/Control No. 10/523,374		Applicant(s)/Patent Under Reexamination KIM ET AL.	
	Examiner DAVID TUROCY		Art Unit 1792	Page 1 of 1

#### U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-6,632,279	10-2003	Ritala et al.	117/101
*	B	US-5,922,405	07-1999	Kim et al.	427/248.1
*	C	US-2001/0041250	11-2001	Werkhoven et al.	428/212
	D	US-			
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	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

#### FOREIGN PATENT DOCUMENTS

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	N					
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#### NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	An et al., "Preparation of Al <sub>2</sub> O <sub>3</sub> Thin Films by Atomic Layer Deposition Using Dimethylaluminum Isopropoxide and Water and Their Reaction Mechanism", Bull. Korean Chem. Soc. 2003 Vol. 24, No. 11. Received July 1, 2003.
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\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
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